

Title (en)
Positive photoresist composition

Title (de)
Positive arbeitende Photolackzusammensetzung

Title (fr)
Composition pour photoréserve positive

Publication
EP 0443533 B1 19980930 (EN)

Application
EP 91102371 A 19910219

Priority
JP 3929990 A 19900220

Abstract (en)
[origin: EP0443533A2] A positive photoresist composition is disclosed containing (A) an alkali-soluble resin, (B) (a) 1,2-naphthoquinonediazido-5-(and/or -4-)sulfonate(s) of an aromatic hydroxy compound having one hydroxyl group in one molecule, and (C) (a) 1,2-naphthoquinonediazido-5-(and/or -4-)sulfonate(s) of an aromatic polyhydroxy compound having 4 or more hydroxyl groups in one molecule, the ratio of (B)/(C) being from 5/95 to 35/65. The composition has high resolving power and sensitivity and forms a resist pattern having a good cross sectional shape. It is useful for the manufacture of semiconductor devices, being free from the problems of development failure and having excellent storage stability.

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G03F 7/022

IPC 8 full level
G03F 7/022 (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP)
G03F 7/022 (2013.01)

Cited by
DE4324654B4; EP0644460A1; EP0737895A1; US5723254A; US6790582B1; US9045405B2; AU2009274158B2; AU2016203045B2; US9126913B2; US10548825B2; US6905809B2; US9096507B2; US9682910B2

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